

# MRS Issues Statement on MS&E Study Report

Speaking on behalf of the Materials Research Society, 1989 MRS President R.P.H. Chang announced in December that

"The Materials Research Society applauds the study report on Materials Science and Engineering recently released by the National Research Council for the National Academies. MRS believes that this study succinctly captures the needs and opportunities of the field for the 1990s and hopes broad support from the materials community is forthcoming to aid in the implementation of study recommendations."

President Chang went on to urge all materials-related technical societies to take an active role on behalf of the community in pursuing implementation.

Expanding on the Society statement, Kathleen C. Taylor, chair of the MRS External Affairs Committee, said that the roles of technical societies "should be both individual and collective. Individual roles would include traditional activities such as in the area of continuing education. For MRS, in particular, continuing education means specialized instruction in emerging areas of the field."

She further stated that another tradi-

tional activity is the facilitation of communication through meetings and publications. All of the available, most effective communication media should be exploited. At its recent Fall meeting, for example, MRS took a first step with a satellite broadcast of its Symposium X, a series of overview lectures for the nonspecialist in several frontier areas of materials research. Many other opportunities exist for which a more effective role for the technical societies would be collective or cooperative.

"To bring the full breadth and excitement of our field to the educational challenge and to demonstrate to policymakers the vital role of materials science and engineering for the national welfare, societies must coordinate and pool their efforts in order to be effective," Taylor emphasized.

"The Materials Research Society is eager to work with other societies toward the formidable changes required to put the recommendations of the MS&E Study in place."

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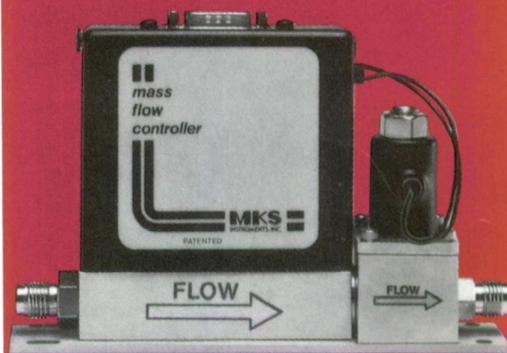
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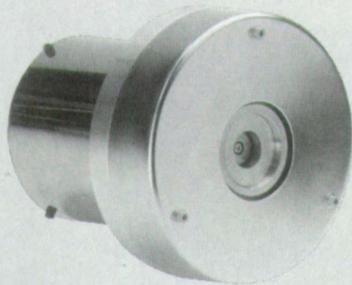
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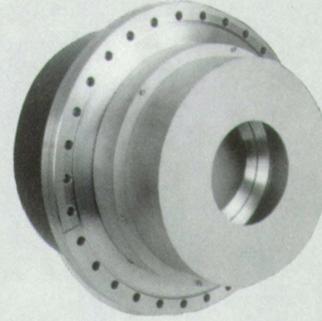
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† VLSI Research, Inc. 1988

‡ See technical papers by Cumo of IBM and Clarke of SFI for discussion of negative ion effect during reactive sputtering of oxides.

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